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Practice for dosimetry in an electron beam facility for radiation processing at energies between 300 keV and 25 MeV

Pratique de la dosimétrie dans une installation de traitement par irradiation utilisant un faisceau d'électrons d'énergies comprises entre 300 keV et 25 MeV

Reference number
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Foreword

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ASTM International is one of the world's largest voluntary standards development organizations with global participation from affected stakeholders. ASTM technical committees follow rigorous due process balloting procedures.

A project between ISO and ASTM International has been formed to develop and maintain a group of ISO/ASTM radiation processing dosimetry standards. Under this project, ASTM Committee E61, Radiation Processing, is responsible for the development and maintenance of these dosimetry standards with unrestricted participation and input from appropriate ISO member bodies.

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. Neither ISO nor ASTM International shall be held responsible for identifying any or all such patent rights.

International Standard ISO/ASTM 51649 was developed by ASTM Committee E61, Radiation Processing, through Subcommittee E61.03, Dosimetry Application, and by Technical Committee ISO/TC 85, Nuclear energy, nuclear technologies and radiological protection.

This third edition cancels and replaces the second edition (ISO/ASTM 51649:2005), which has been technically revised.

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